

- The optical constants for the layer was compared to bulk Ge.
- determine the critical point parameters.

- most of the native oxide before performing ellipsometry measurements.

- pure Ge layer, a GeO_2 oxide, and air as the ambient.











Optical and X-ray Characterization of Ge_{1-v}Sn_v Alloy on GaAs

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Conclusion:

- the tin content is y=0.012.
- The (224) reciprocal space maps allow us to find that the alloy layer was grown pseudomorphically on
- the GaAs substrate despite the large thickness.
- thickness is 1600 nm.
- broadening, and phase angle.
- phase angle fixed to be the same.

References:

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<u>Relaxed:</u>	
$E_1^{GeSn} = y E_1^{Sn} + (1 - y) E_1^{Ge} - b_{GeSn} y (1 - y)$	
$(E_1 + \Delta_1)^{GeSn} = y(E_1 + \Delta_1)^{Sn} + (1 - y)(E_1 + \Delta_1)^{Sn}$	$b^{Ge} - b_{GeSn}y(1 - $
$b_{GeSn} = 1.350 \text{ eV}$	
<u>Strained:</u>	
$E_1^{GeSn} = E_1^{\text{Relaxed}} + \Delta E_H - \frac{\Delta E_S^2}{\Delta_1}$	small shear approximation
$(E_1 + \Delta_1)^{GeSn} = (E_1 + \Delta_1)^{Relaxed} + \Delta E_H + \frac{\Delta E_S^2}{\Delta_1}$	$\Delta E_s \ll \Delta_1$
$\Delta E_H = \sqrt{3} \left[y D_1^{1 Sn} + (1 - y) D_1^{1 Ge} \right] \varepsilon_H$	
$D_1^{1 Sn} = -5.4 \text{ eV}, \ D_1^{1 Ge} = -8.7 \text{eV}, \ \ arepsilon_H = rac{arepsilon_\perp}{-1}$	$\frac{+2\varepsilon_{ }}{3}$

 $\Delta E_S = \sqrt{6} \left[y D_3^{3 Sn} + (1 - y) D_3^{3 Ge} \right] \varepsilon_S$ $D_3^{3 Sn} = -3.8 \text{ eV}, \ D_3^{3 Ge} = -5.6 \text{ eV}, \ \varepsilon_S = \frac{\varepsilon_{\perp} + \varepsilon_{||}}{3}$

Using Vegard's Law, continuum elasticity theory, and the (004) reciprocal space map, we determine that

After modeling the ellipsometry data, we found that the oxide thickness is 2.6 nm and the epilayer

The point-by-point fit of the $Ge_{1-y}Sn_y$ dielectric function was very similar to bulk Ge. Using the second derivative, we found the critical point parameters, including amplitude, energy,

 E_1 is found to have a slightly higher energy in $Ge_{1-y}Sn_y$ than in bulk Ge. That is puzzling, even with the

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